



ZEN AF

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: 2851
Examiner: Peter B Kim

In Re PATENT APPLICATION Of:

Applicant: Mark C. HAKEY et al.)
Serial No.: 10/808,740)
Filed: March 25, 2004)
For: System and Apparatus for Photolithography)
Attny Ref.: ROC920040026US1-IBM 230)

**RESPONSE AFTER
FINAL REJECTION**

**SUBMISSION OF
TERMINAL
DISCLAIMER**

October 19, 2005

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This paper is in response to the Official Action mailed on September 22, 2005. No fee is due. However, please charge our Deposit Account No. 18-0002 if any fees are needed to enter this paper, and please advise us accordingly. It is noted that no petition is required because of the authorization to charge, but please consider this paper a petition for extension of time if needed.

Of the pending claims, Claims 1-20 are rejected for obviousness-type double patenting. A terminal disclaimer is attached hereto, which overcomes the rejection. The case is therefore believed to be in condition for allowance, which is requested.

Respectfully submitted,

Nicholas S. Bromer (Reg. No. 33,478)
RABIN & BERDO, P.C.
CUSTOMER NO. 23995
Tel: (202) 371-8976
Fax: (202) 408-0924

October 19, 2005

Date

FEE ENCLOSED: \$ 130
Please charge any further
fee to our Deposit Account
No. 18-0002